Notice of Allowability	Application No.	Applicant(s)	
	10/600,650	HIDAKA ET AL.	
	Examiner	Art Unit	
	Phat X. Cao	2814	
The MAILING DATE of this communication apperature All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in or other appropriate common GHTS. This application is so	n this application. If not included unication will be mailed in due course. THI	
1. This communication is responsive to 6/23/03.			
2. The allowed claim(s) is/are <u>19-22</u> .			
3. $\boxtimes$ The drawings filed on <u>23 June 2003</u> are accepted by the E	xaminer.		
<ul> <li>4.  Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).</li> <li>a)  All b)  Some* c)  None of the: <ol> <li>Certified copies of the priority documents have been received.</li> <li>Certified copies of the priority documents have been received in Application No. 08/596,798.</li> <li>Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)).</li> </ol> </li> <li>* Certified copies not received:</li> </ul>			
Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application.  THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.			
5. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.			
6. CORRECTED DRAWINGS ( as "replacement sheets") mus	st be submitted.		
(a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review ( PTO-948) attached			
1)  hereto or 2) to Paper No./Mail Date			
(b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date			
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t	.84(c)) should be written on t he header according to 37 CF	ne drawings in the front (not the back) of R 1.121(d).	
7. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.			
<ul> <li>Attachment(s)</li> <li>1. ☑ Notice of References Cited (PTO-892)</li> <li>2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)</li> <li>3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 6/23/03</li> <li>4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material</li> </ul>	6. ☐ Interview S Paper No. 7. ☒ Examiner's	formal Patent Application (PTO-152) ummary (PTO-413), /Mail Date Amendment/Comment Statement of Reasons for Allowance	

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## **EXAMINER'S AMENDMENT**

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

## **IN THE SPECIFICATION:**

On page 1, inserting before the first line, the following sentence:

This application is a DIV of 09/370,220, filed 08/09/1999, Patent No. 6,586,803, which is a DIV of 08/977,030, filed 11/25/1997, Patent No. 5,982,005, which is a CON of 08/596,798, filed 02/05/1996, now abandoned.

2. The following is an examiner's statement of reasons for allowance: the prior art of record fails to disclose the combination of a semiconductor device structure recited in the base claims 19 and 21, including the combination of the structure comprising: an SOI substrate; a field shield structure formed on the SOI substrate; an interlayer insulation film formed on the field shield structure; and a bonding pad formed on the interlayer insulation film. The prior art of record also fails to disclose the combination of a semiconductor device structure recited in the base claim 22, including the combination of the structure comprising: an SOI substrate; a first and second element isolation regions formed on the buried insulation layer of the SOI substrate; an interlayer

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insulation film formed between the first and second element isolation regions; and a bonding pad formed on the interlayer insulation film.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Phat X. Cao whose telephone number is (571) 272-1703. The examiner can normally be reached on Monday - Thursday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael Fahmy can be reached on (571) 272-1705. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

PC

PRIMARY EXAMINER

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